

August 5, 2003  
Application No. 09/848,904

**Amendments to the Specification**

Please replace the paragraph on page 7, lines 20-25, with the following amended paragraph:

To maintain the hydrogen-free environment, the dopant material 26 is preferably free of hydrogen. Similarly, to maintain a chlorine-free environment, the dopant material 26 is preferably free of chlorine. U.S. Application Serial No. [[\_\_\_\_\_,]] 09/848,903, entitled "Method and Feedstock for Making Silica," filed [[\_\_\_\_\_,]] May 4, 2001, in the name of David L. Tennent and J. Mare Joseph M. Whalen, discloses a chlorine-free germania dopant which comprises a pseudohalogen, e.g.,  $\text{Ge}(\text{NCO})_4$ .